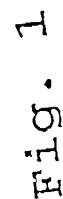
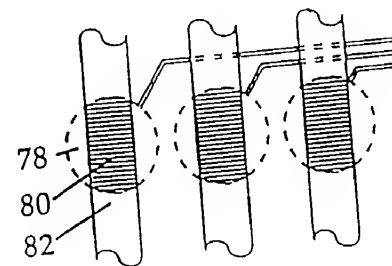
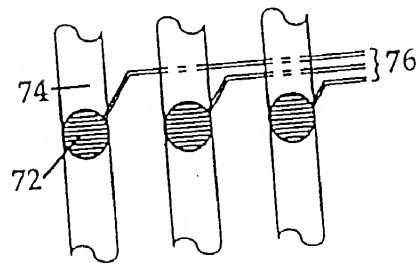
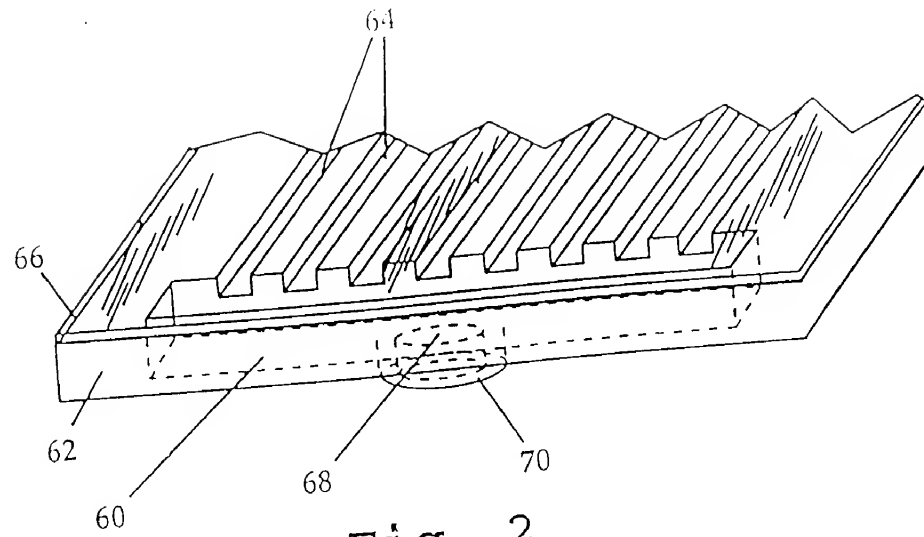


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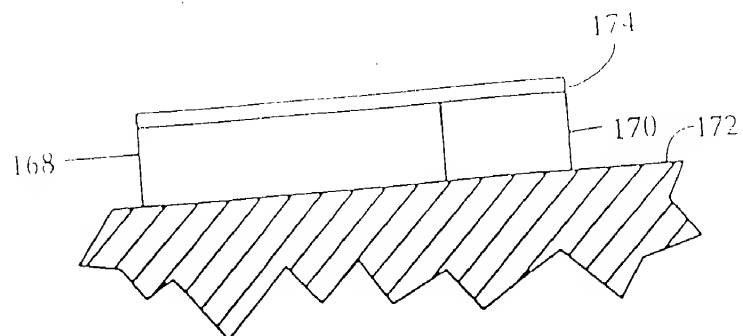


Fig. 4A

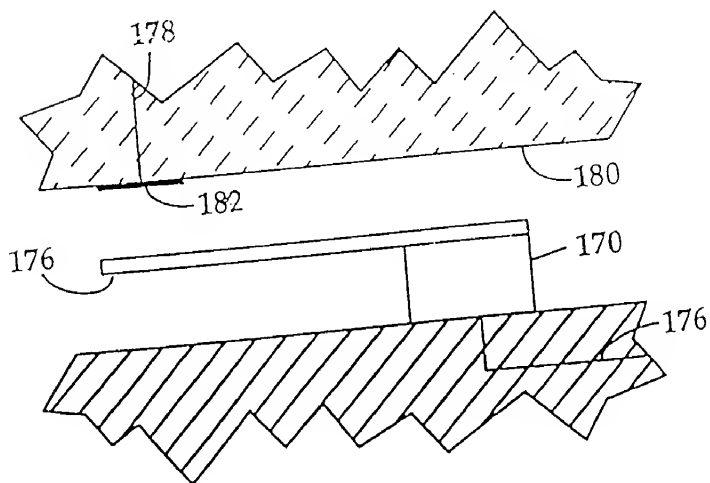


Fig. 4B

00827-34542460

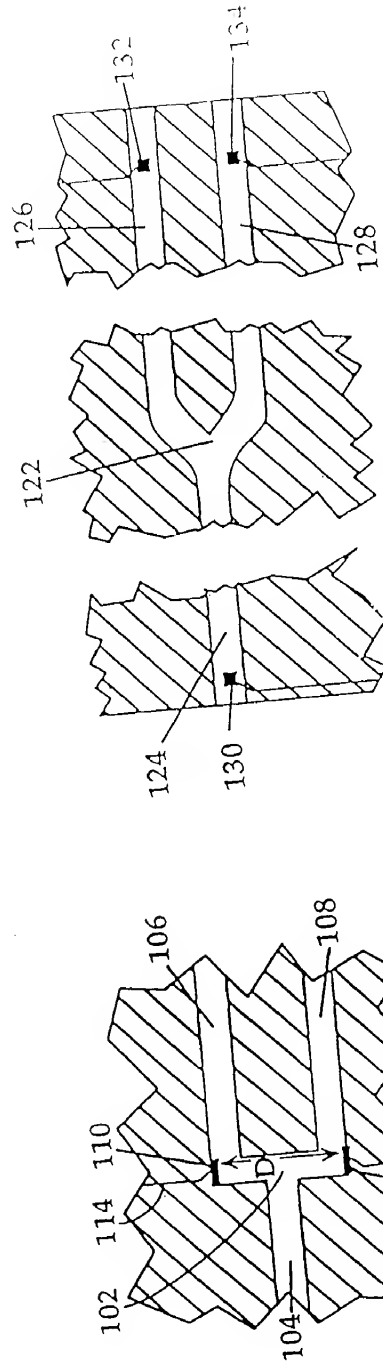


Fig. 5A

Fig. 5B

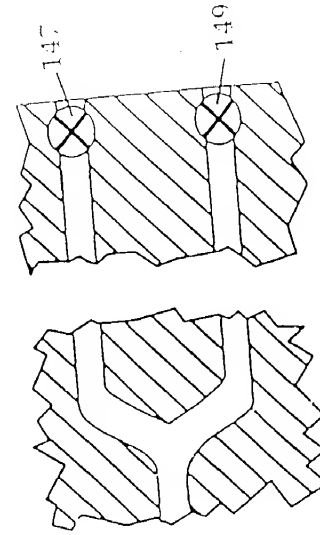


Fig. 5C

Fig. 5D

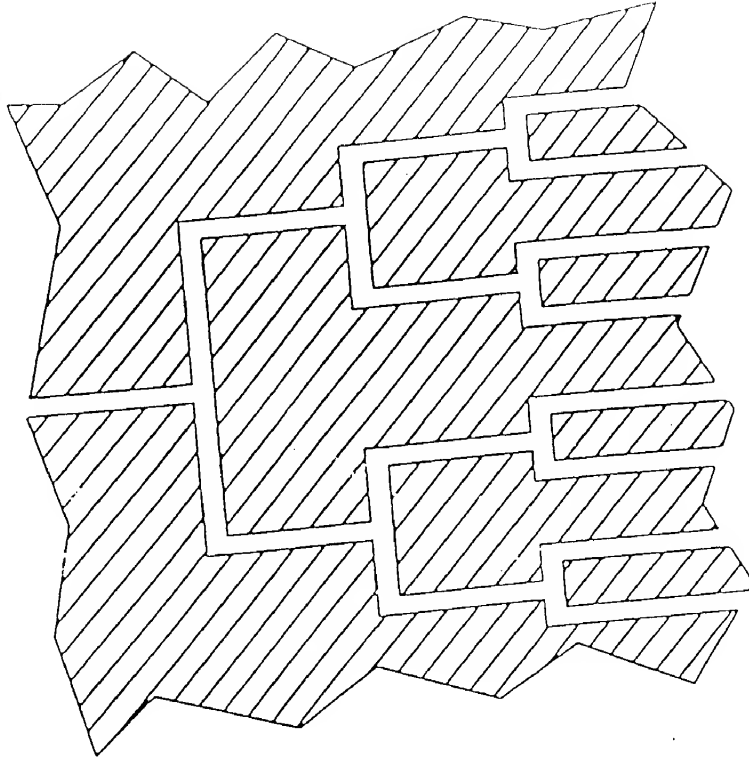


Fig. 6

00821-84512/60

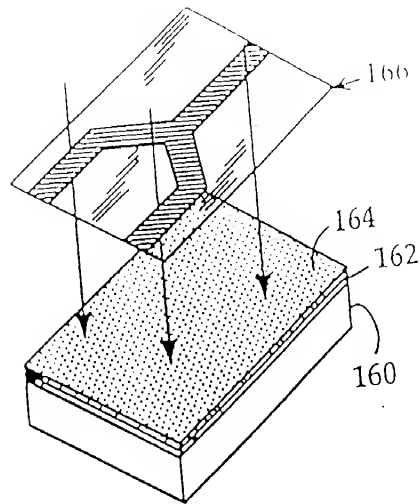


Fig. 7A

develop
→
and rinse

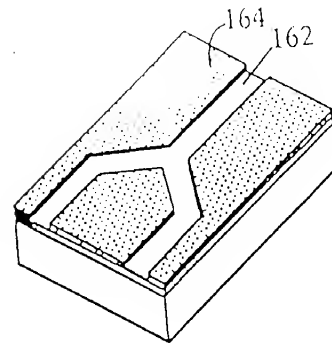


Fig. 7B

1. etch SiO_2
2. remove resist

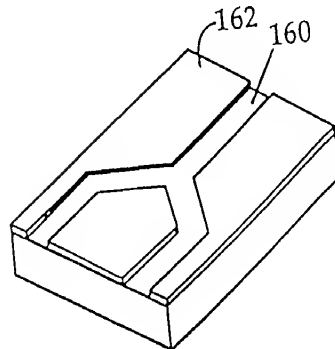


Fig. 7c

etch Si

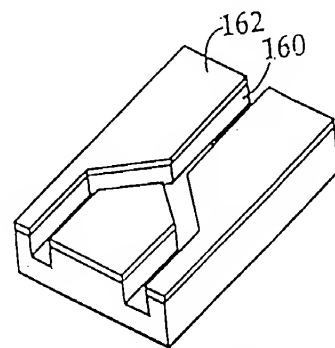


Fig. 7D

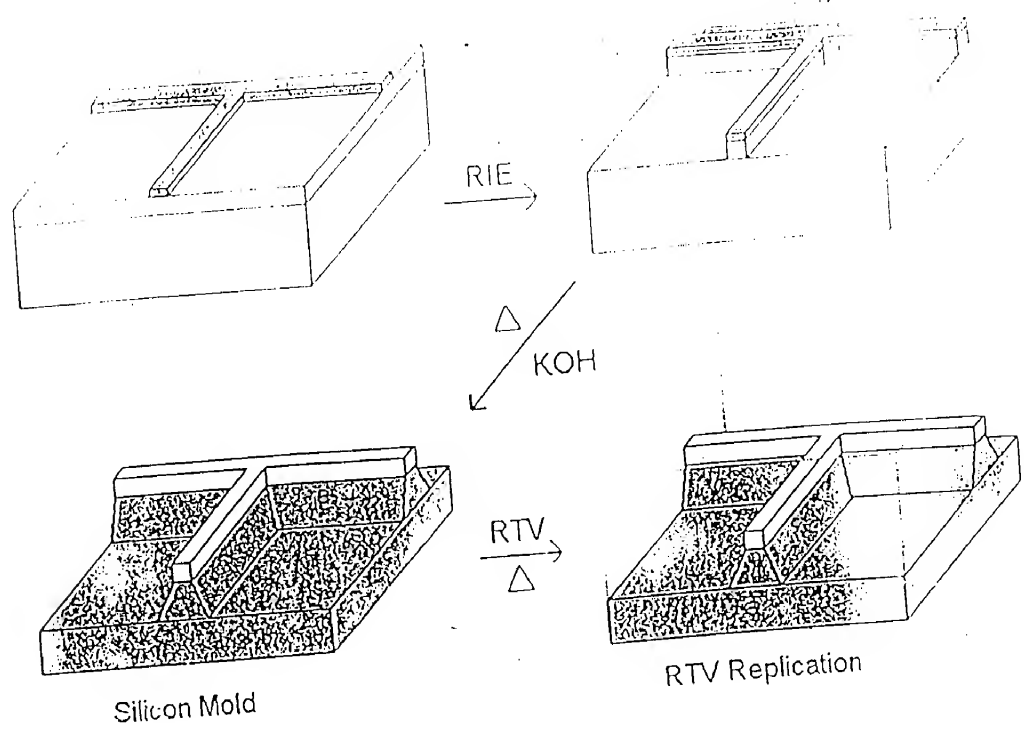
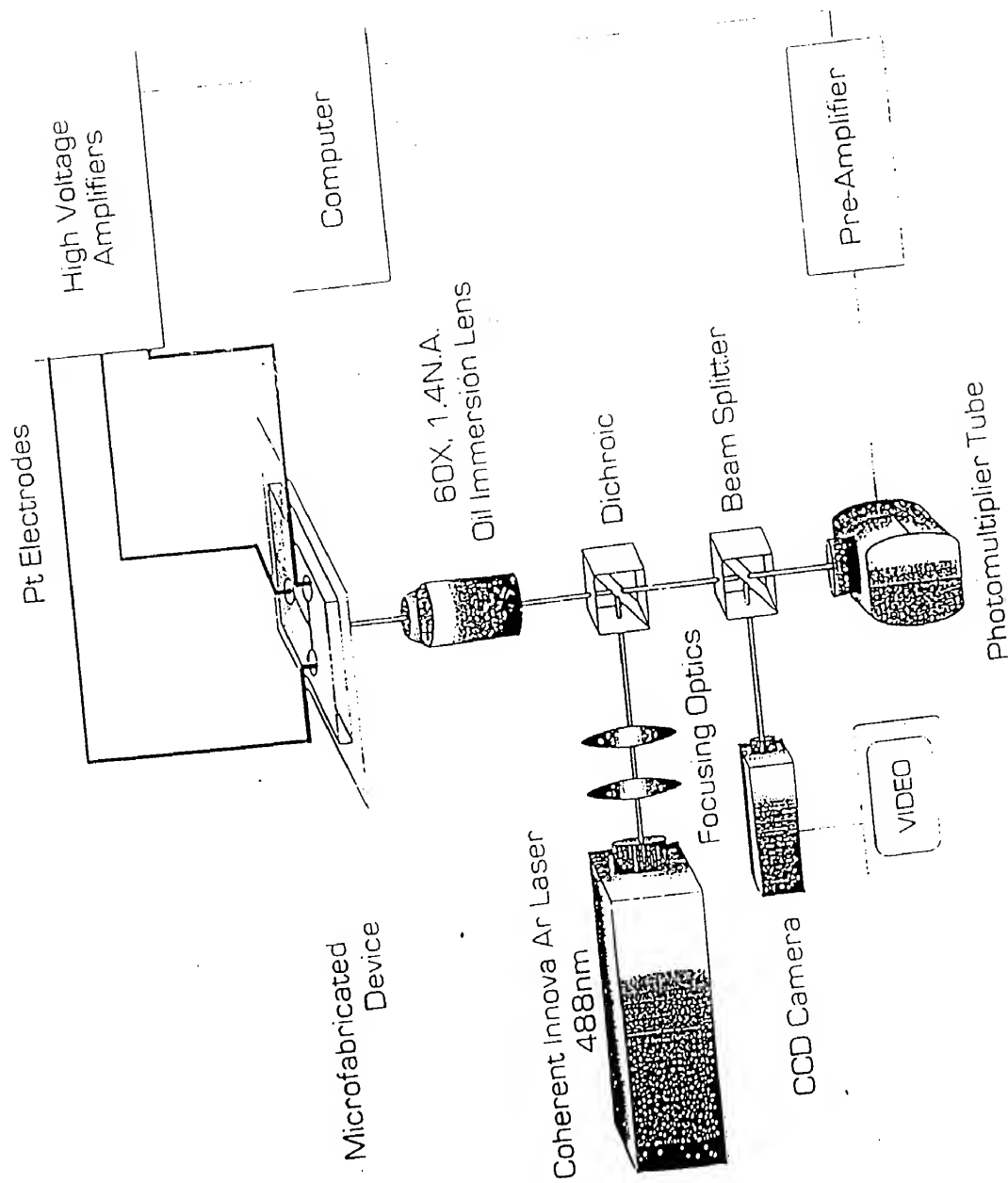


Fig. 8

09724548.11300

003211 3154260

(SHEET 8 OF 21)



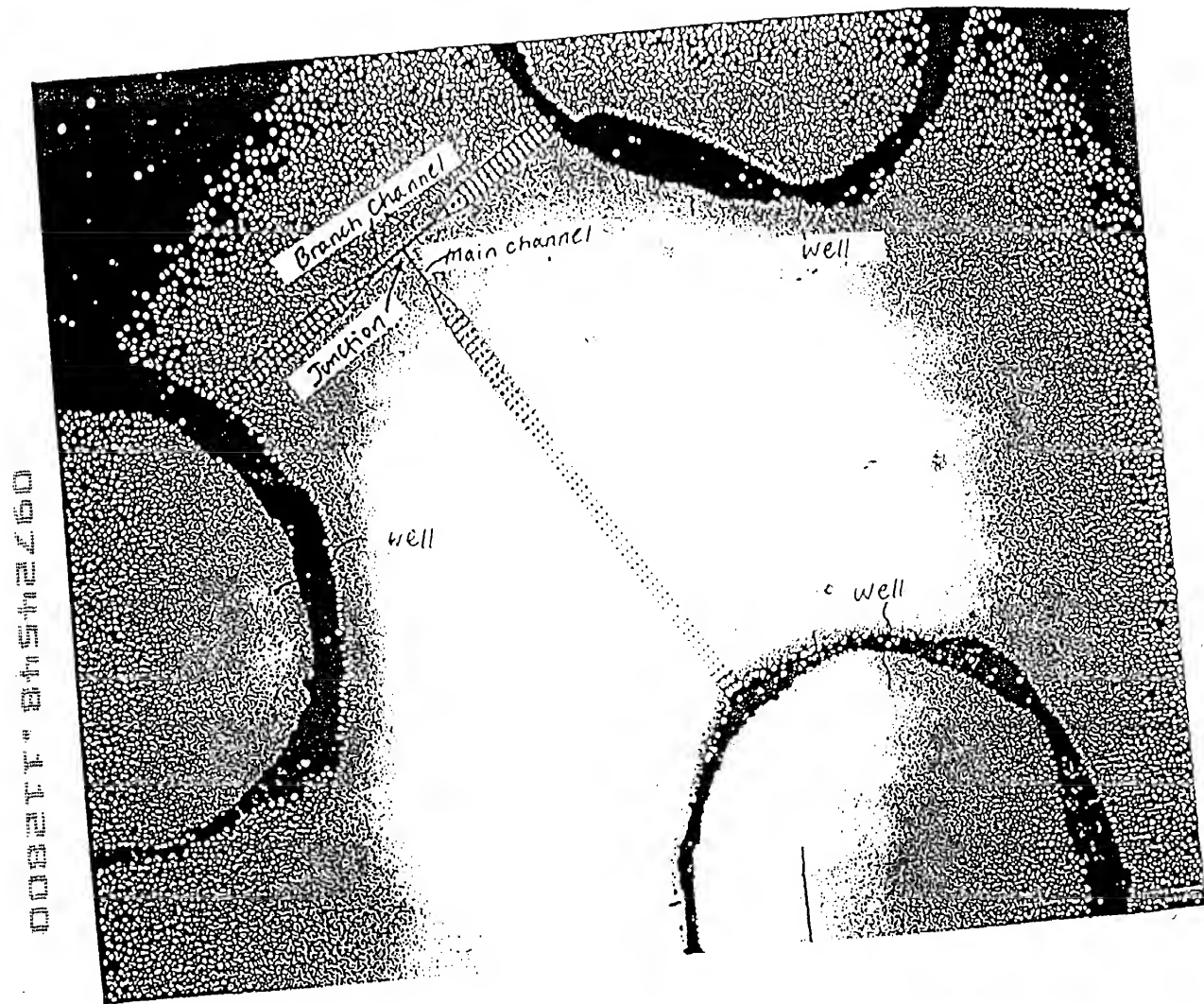


Fig 10

Fig. 11

Sheet 10 of 21

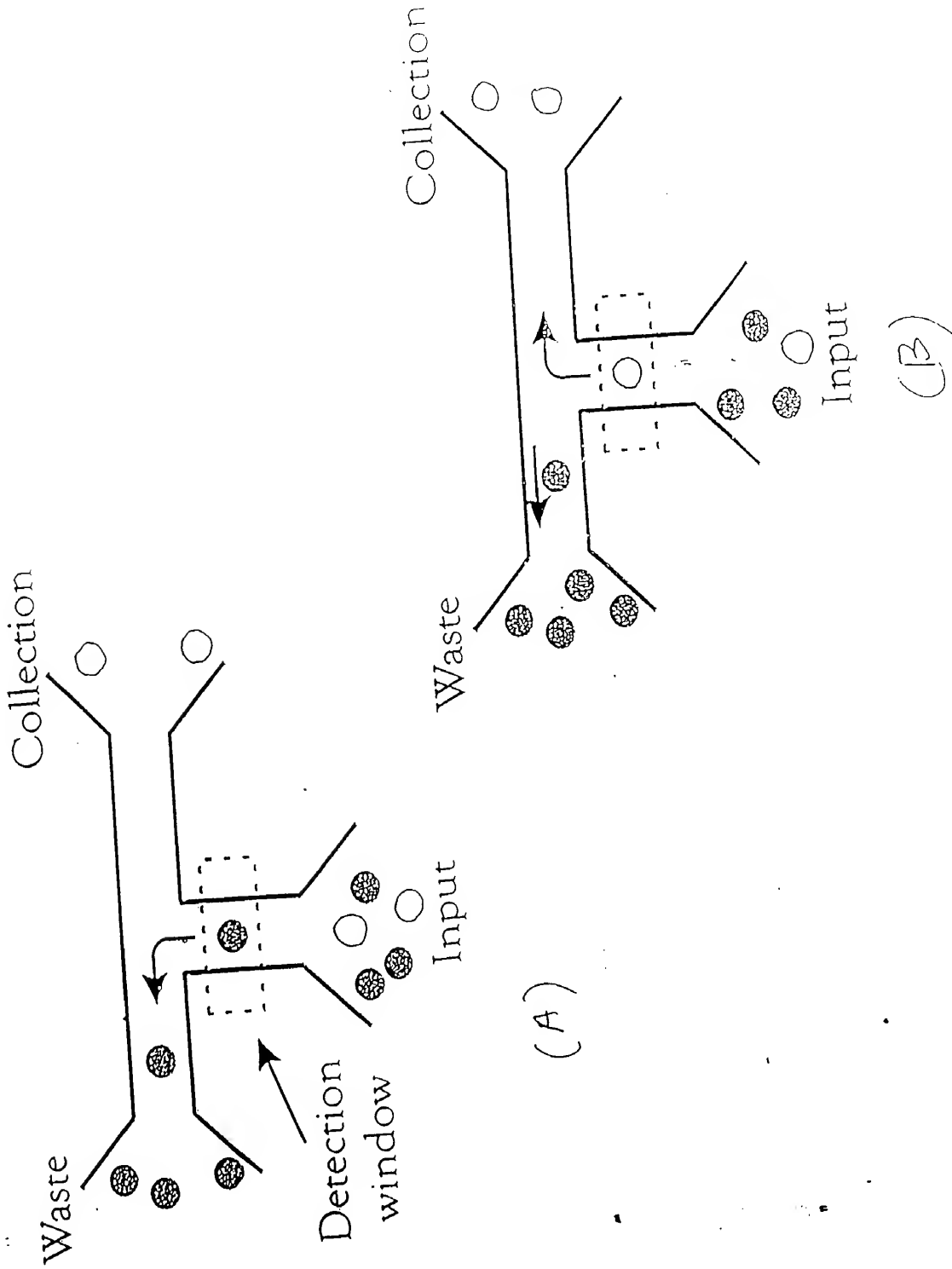
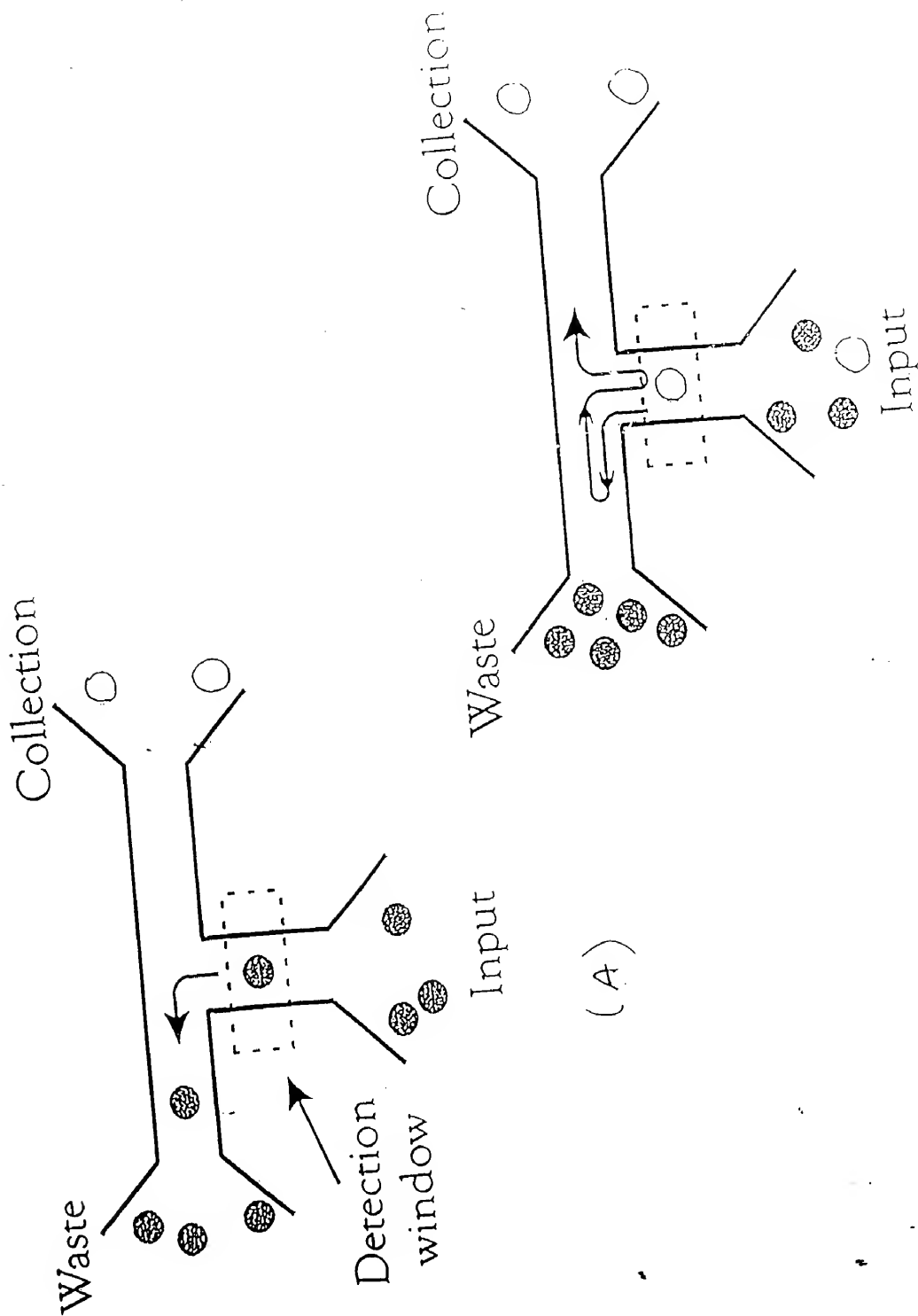


Fig 12



(B)

(A)

FIG. 14

Sheet 13 of 21

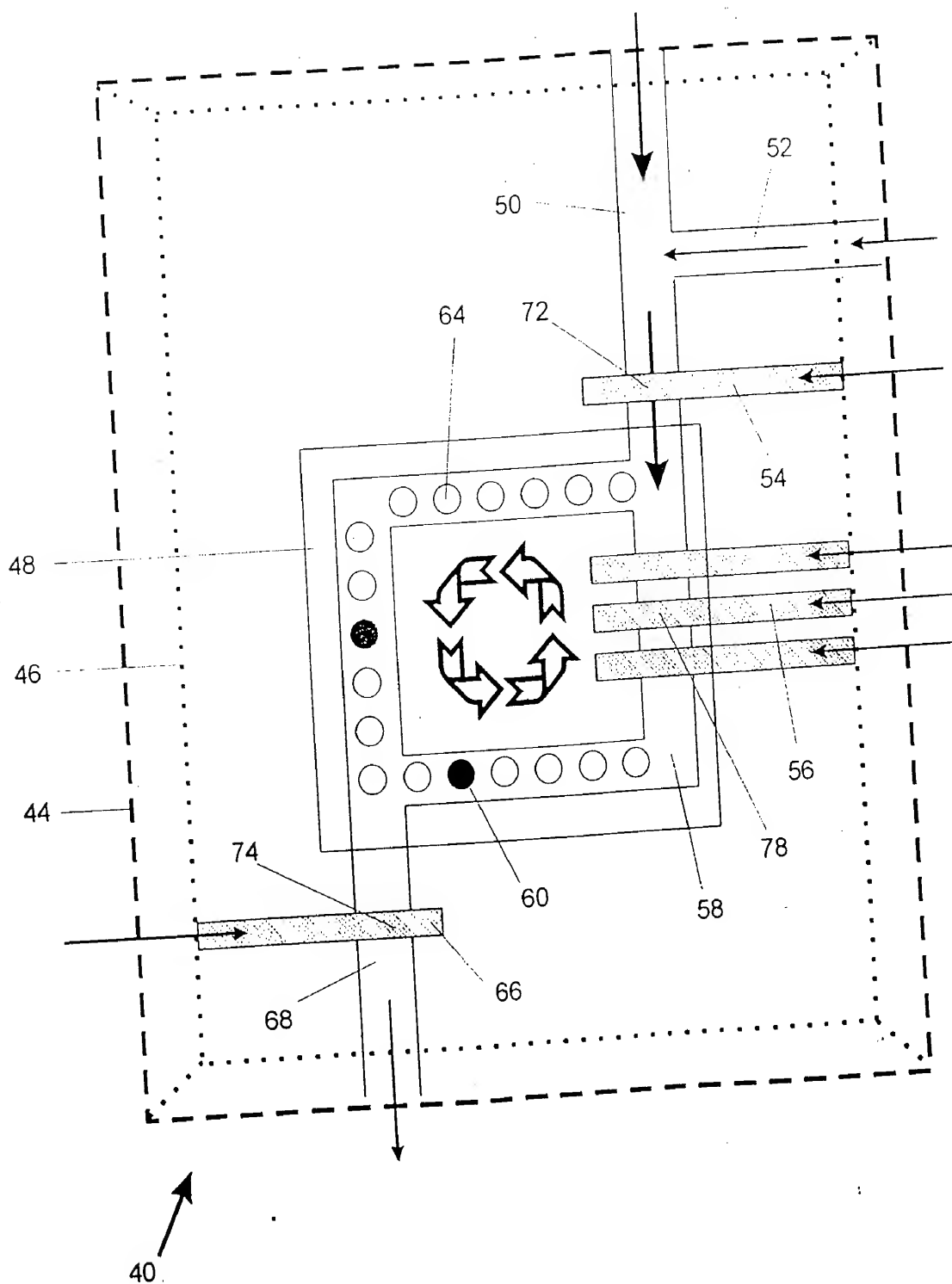


FIG. 15

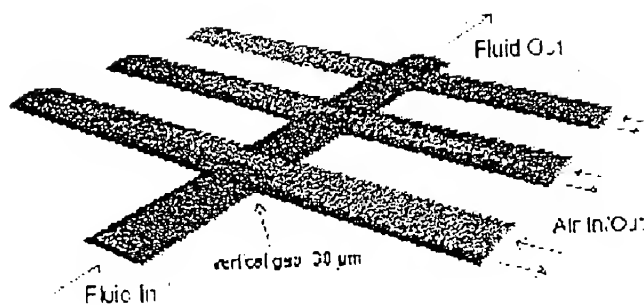
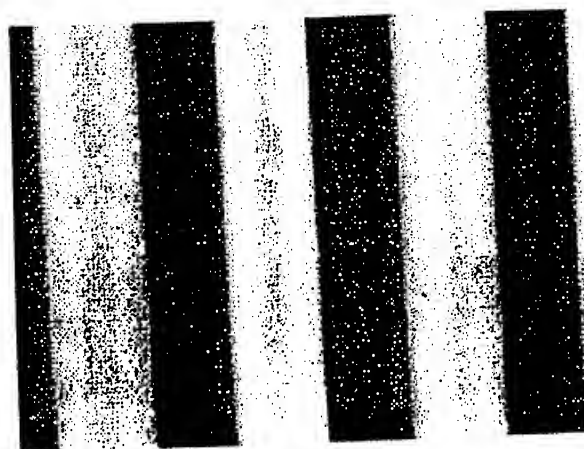


FIG. 16A



008211 0454260

FIG. 16B

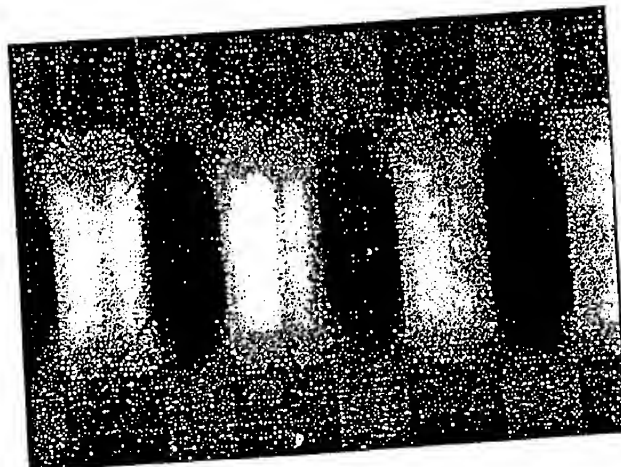
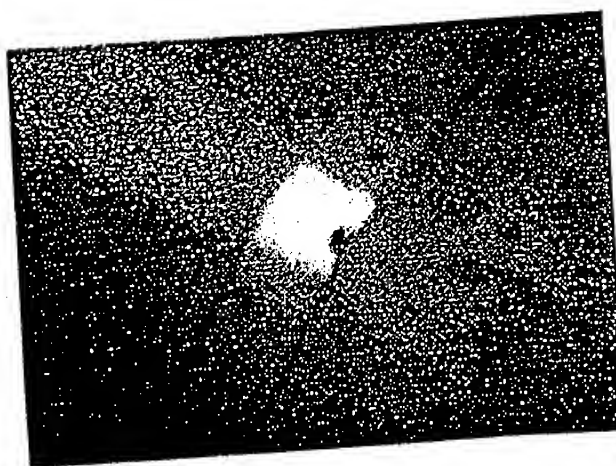
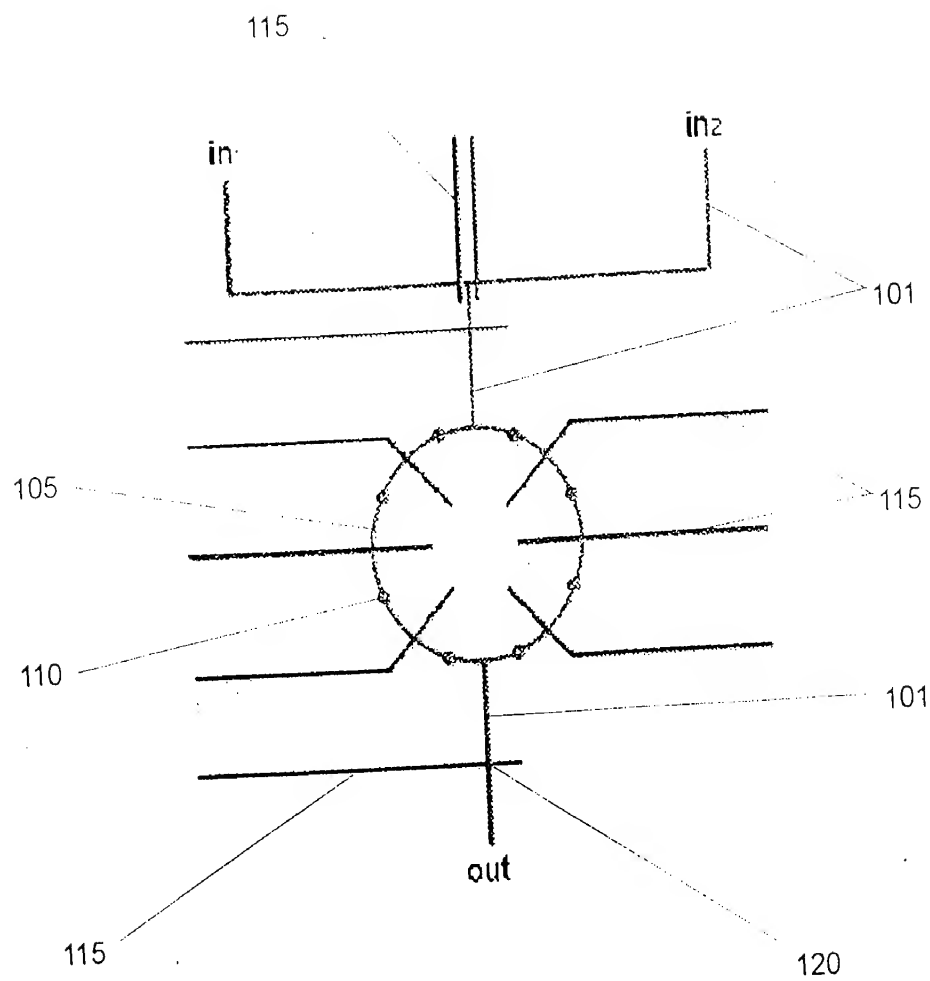


FIG. 16C



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FIG. 17



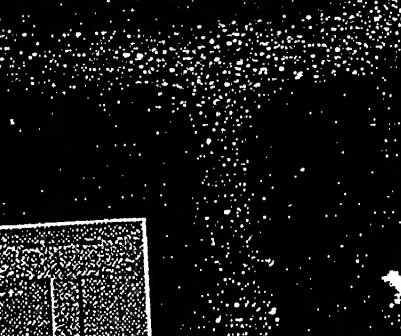
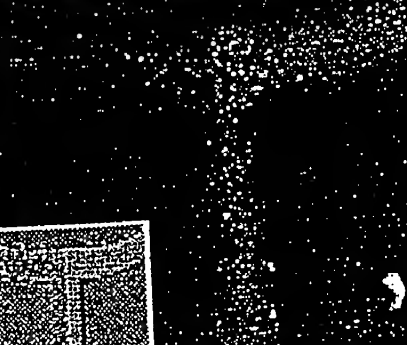
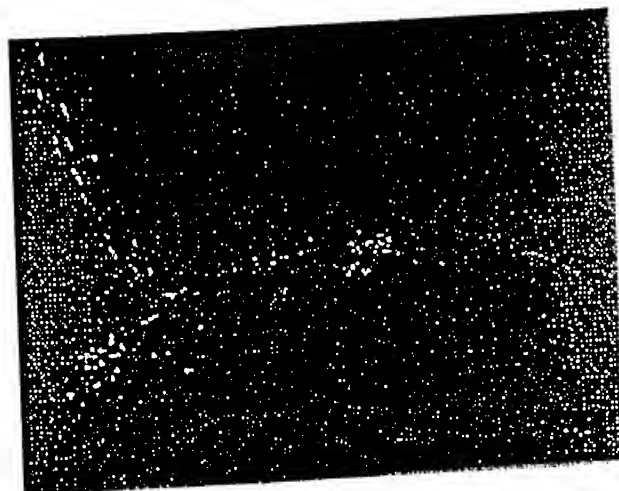


FIG. 19



09724548-112300



FIG. 20

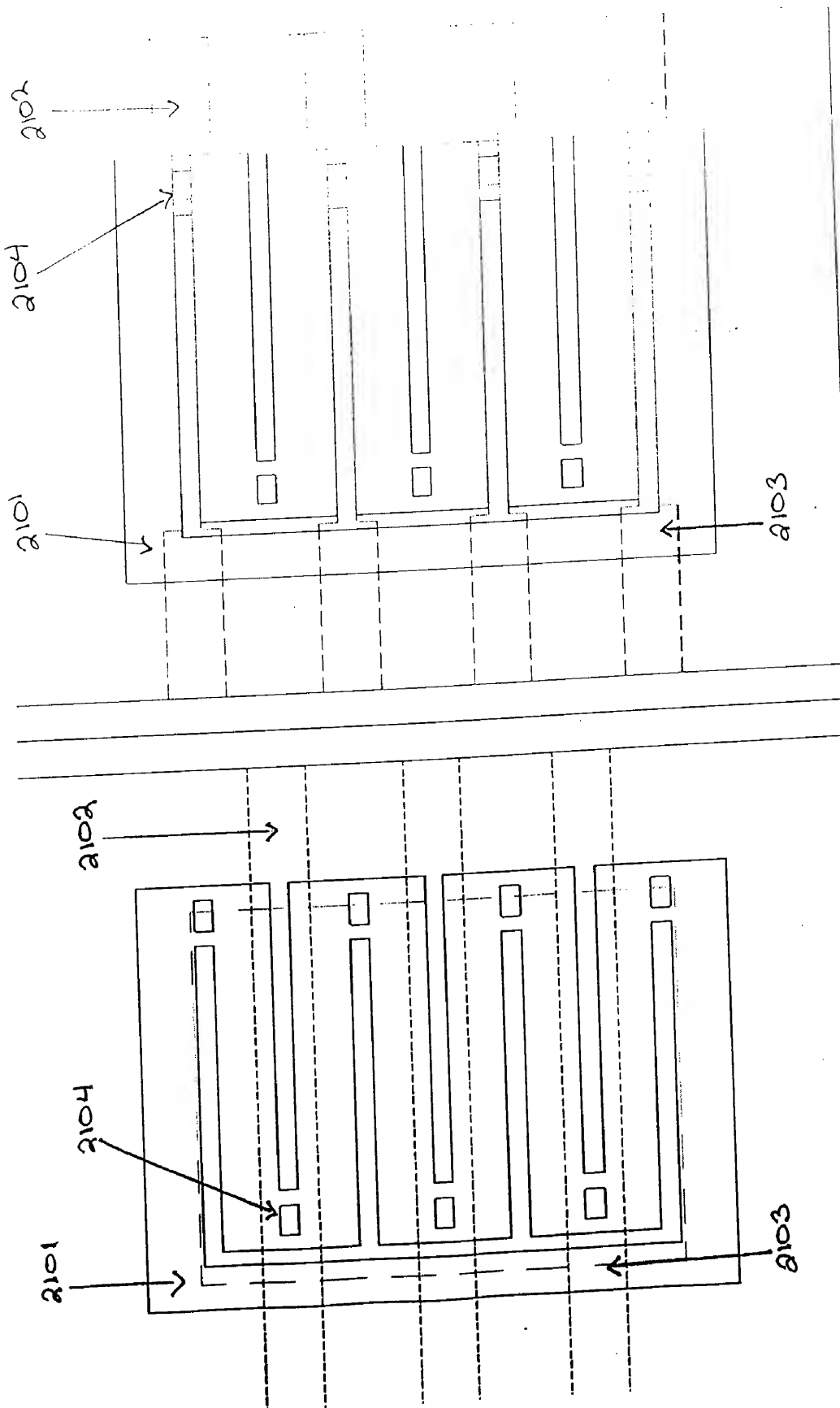


FIG. 21A

FIG. 21B

FIG. 22A

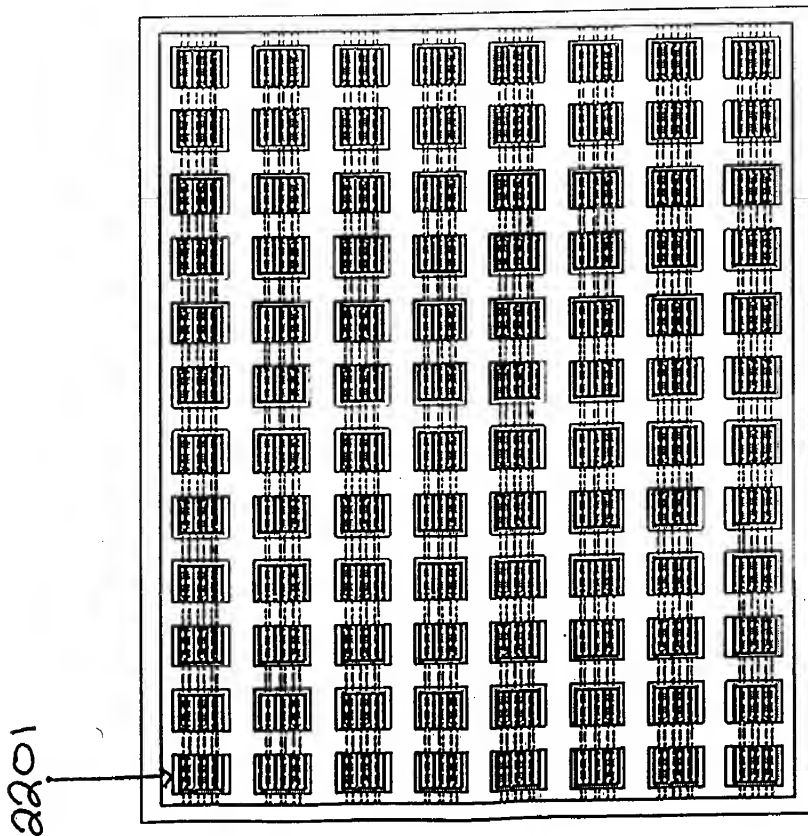


FIG. 22A

2201 2203 2202

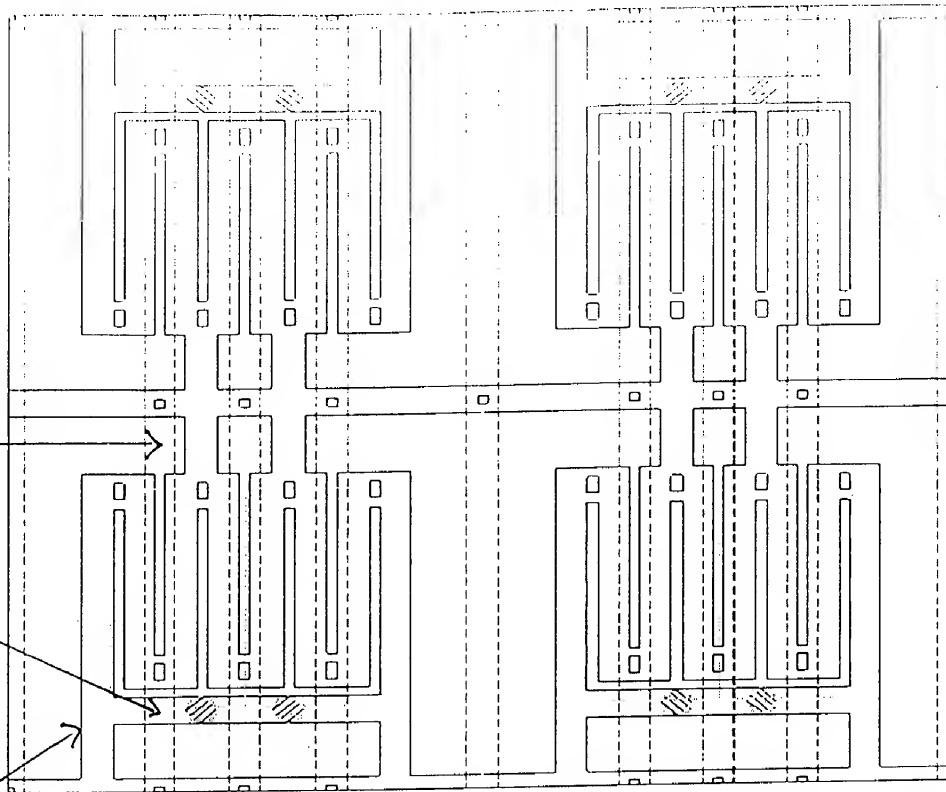


FIG. 22B